

## EAST Search History

## EAST Search History (Prior Art)

| Ref # | Hits | Search Query  | DBs  | Default Operator | Plurals | Time Stamp       |
|-------|------|---|--|------------------|---------|------------------|
| L1    | 4377 | (room adj temperature) near5 (ambient adj temperature)  | US-PGPUB; USPAT  | OR               | ON      | 2009/12/26 16:21 |
| L2    | 4788 | (room adj temperature) near5 (ambient adj temperature)  | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR               | ON      | 2009/12/26 16:22 |
| L3    | 0    | (room adj temperature) near3 (ambient adj temperature)with (lithography)  | US-PGPUB; USPAT  | OR               | ON      | 2009/12/26 16:23 |
| L4    | 1    | (room adj temperature) near3 (ambient adj temperature) same (lithography)   | US-PGPUB; USPAT  | OR               | ON      | 2009/12/26 16:24 |
| L5    | 2    | (room adj temperature) near3 (ambient adj temperature) same (lithograph\$ or photolithograph\$)   | US-PGPUB; USPAT  | OR               | ON      | 2009/12/26 16:24 |
| L6    | 0    | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) near5 (deposit or residue or film or contaminant or impurity or particle or particulate) with ((room or ambient) adj4 temperature) same (lithograph\$ or photolithograph\$) | US-PGPUB; USPAT  | OR               | ON      | 2009/12/26 17:11 |

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| L7  | 0   | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) near5 (deposit or residue or film or contaminant or impurity or particle or particulate or contamination) with ((room or ambient) adj4 temperature) same (lithograph\$ or photolithograph\$) | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:12 |
| L8  | 0   | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) with ((room or ambient) adj4 temperature) same (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:12 |
| L9  | 7   | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) with ( temperature) same (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:12 |
| L10 | 233 | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) with ( temperature) and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:13 |
| L11 | 195 | l10 and (wafer or semiconductor or silicon)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:14 |
| L12 | 18  | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) with ( ( room or ambient) near5 temperature) and (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:16 |
| L13 | 19  | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 (carbon\$6) with ( ( room or ambient) near5 temperature) and (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:21 |

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| L14 | 19    | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 (carbon or carbonaceous) with ( ( room or ambient) near5 temperature) and (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:21 |
| L15 | 8     | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 (carbon or carbonaceous or carbon adj gas or carbon adj monoxide or carbon adj dioxide or "CO" or "CO.sub.2" or "CO2") with (temperature or centigrade or celcius) same (lithograph\$ or photolithograph\$) | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:33 |
| L16 | 18994 | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 (carbon or carbonaceous or carbon adj gas or carbon adj monoxide or carbon adj dioxide or "CO" or "CO.sub.2" or "CO2") with (temperature or centigrade or celcius)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:35 |
| L17 | 9547  | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 ( carbon adj gas or carbon adj monoxide or carbon adj dioxide or "CO" or "CO.sub.2" or "CO2") with (temperature or centigrade or celcius)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:35 |
| L18 | 147   | 117 and (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:35 |

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| L19 | 129  | 118 and (wafer or semiconductor or silicon or mask)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:36 |
| L20 | 7239 | (oxidation or oxidizing or oxidized or oxidize or oxidant) near5<br>( carbon adj gas or carbon adj monoxide or carbon adj dioxide or "CO" or "CO.sub.2" or "CO2") with<br>(temperature or centigrade or celcius) | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:38 |
| L21 | 106  | 120 and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:39 |
| L22 | 652  | ("CO" ) near5 (oxidize or oxidation or oxidizing or oxidized)<br>with (low) near4<br>(temperature)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:42 |
| L23 | 26   | 122 and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:42 |
| L24 | 740  | (carbon adj dioxide or carbon adj monoxide or "CO.sub.2" or "CO2" ) near5 (oxidize or oxidation or oxidizing or oxidized)<br>with (low) near4<br>(temperature)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:44 |
| L25 | 26   | 123 and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:44 |

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| L26 | 285 | (carbon adj dioxide or carbon adj monoxide or "CO.sub.2" or "CO2" ) near5 (oxidize or oxidation or oxidizing or oxidized) with ((ambient or room) near4 (temperature) or "25 adj C")   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:51 |
| L27 | 174 | (carbon adj dioxide or carbon adj monoxide or "CO.sub.2" or "CO2" ) near5 (oxidize or oxidation or oxidizing or oxidized) near4 ((ambient or room) near4 (temperature) or "25 adj C")  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:51 |
| L28 | 225 | (carbon adj dioxide or carbon adj monoxide or "CO.sub.2" or "CO2" ) near5 (oxidize or oxidation or oxidizing or oxidized) near10 ((ambient or room) near4 (temperature) or "25 adj C") | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:52 |
| L29 | 3   | 128 and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:52 |

**EAST Search History (Interference)**

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**12/ 26/ 2009 5:55:24 PM**